

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventors: James M. Holden; William A. McGahan; Richard A. Yacoubi; Pablo I. Rovira; Roger R. Lowe-Webb
Assignee: Nanometrics Incorporated
Title: Apparatus And Method For The Measurement Of Diffracting Structures
Serial No.: 09/670,000 Filing Date: September 25, 2000
Examiner: Chih-Cheng Glen Kao Group Art Unit: 2882
Docket No.: NAN022 US

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Santa Clara, California
June 13, 2002

COMMISSIONER FOR PATENTS
Washington, D. C. 20231

RESPONSE TO OFFICE ACTION

Dear Sir:

This Response to Office Action is responsive to the March 14, 2002 Office Action, which has a statutorily shortened period for response that ends June 14, 2002. Please enter the following amendments before taking action on the merits of the above-referenced application.

In the Specification

Please replace the paragraph at page 26, line 10 to line 22 with the following paragraph:

ABSTRACT

A normal incidence reflectometer includes a rotatable analyzer/polarizer, which permits measurement of a diffracting structure. Relative rotation of the analyzer/polarizer with respect to the diffracting structure permits analysis of the diffracted radiation at multiple polarity orientations. A spectograph detects the intensity of the spectral components at different polarity orientations. Because the normal incidence reflectometer uses normally incident radiation and an analyzer/polarizer that rotates relative to the diffracting structure, or vice-versa, the orientation of the diffracting structure does not affect the accuracy of the

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